

Supplementary Materials

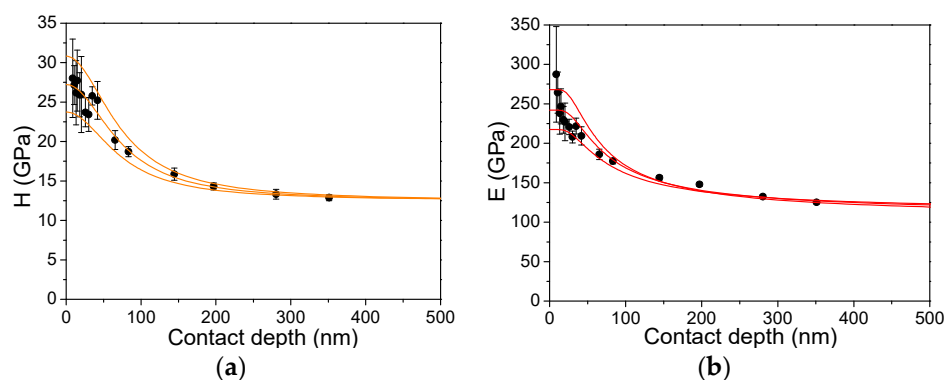


Figure S1. Dependence of (a) hardness and (b) Young's modulus on the indentation depth for the LPCVD BC_xN_y films ($T_{\text{dep}}=773$ K).

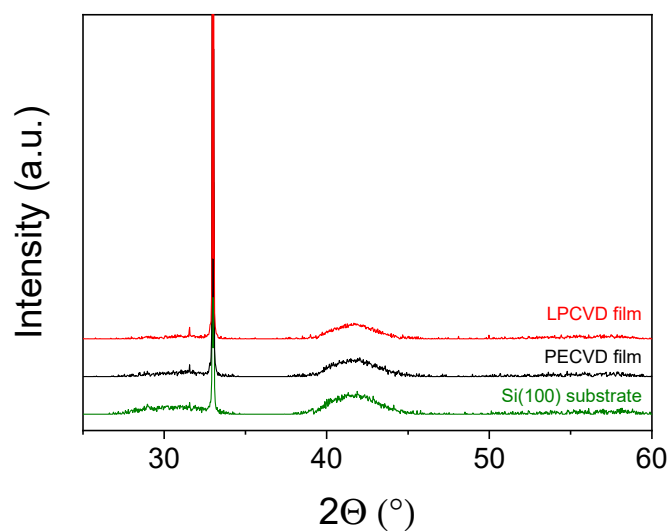


Figure S2. XRD patterns of Si(100) substrate and BC_xN_y films deposited by LPCVD and PECVD processes at 973 and 523 K, respectively.